| L Number | Hits | Search Text | DB | Time stamp |
|---|---|---|---|---|
| 1 | 38 | (((ozone near15 generator) or ozone) near15 (gas or atmosphere)) same (wafer or semiconductor or substrate) same (spray or sprayer or nozzle or jet) same (spin or spinning or rotor or rotate or rotary or turn or rotating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:04 |
| 2 | 3 | (((ozone near15 generator) or ozone) near15 (gas or atmosphere)) same (wafer or semiconductor or substrate) same (spray or sprayer or nozzle or jet) same (spin or spinning or rotor or rotate or rotary or turn or rotating) | USOCR | 2004/04/21 06:04 |
| 3 | 6 | (((ozone near15 generator) or ozone) near15 (gas or atmosphere)) and (wafer or semiconductor or substrate) same (spray or sprayer or nozzle or jet) and (spin or spinning or rotor or rotate or rotary or turn or rotating) | USOCR | 2004/04/21 06:05 |
| 4 | 627 | (((ozone near15 generator) or ozone) near15 (gas or atmosphere)) and (wafer or semiconductor or substrate) same (spray or sprayer or nozzle or jet) and (spin or spinning or rotor or rotate or rotary or turn or rotating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:46 |
| 5 | 26851 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:50 |
| 6 | 9221 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and (wafer or semiconductor or substrate) and (spray or sprayer or nozzle or jet) and (spin or spinning or rotor or rotate or rotary or turn or rotating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:51 |
| 7 | 8938 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and (wafer or semiconductor or substrate) and (spray or sprayer or nozzle or jet) and (spin or spinning or rotor or rotate or rotary or turn or rotating) and (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:56 |
| 8 | 349 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and (wafer or semiconductor or substrate) and (spray or sprayer or nozzle or jet) and (spin or spinning or rotor or rotate or rotary or turn or rotating) and (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USOCR | 2004/04/21 06:57 |
| 9 | 8550 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) and (spray or sprayer or nozzle or jet) and (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:58 |

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| 10 | 8425 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) and ((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent))and (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:00 |
| 11 | 8425 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) and ((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent))and (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:00 |
| 12 | 8331 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) and ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) and (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:01 |
| 13 | 8249 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) same ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) and (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:01 |
| 14 | 8244 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) same ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) same (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:01 |
| 15 | 8239 | (ozone near15 generator) or (ozone near15 (gas or atmosphere))near55 ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) same (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:02 |

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| 16 | 8238 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) near55 ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) near55 (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:08 |
| 17 | 8237 | (ozone near15 generator) or (ozone near15 (gas or atmosphere)) near55 ((wafer or semiconductor or substrate) near15 (spin or spinning or rotor or rotate or rotary or turn or rotating)) near55 (((spray or sprayer or nozzle or jet) near15 (water or liquid or chemical or acid or solution or solvent)) near25 (wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating)) and 134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:10 |
| 18 | 22540 | (ozone near10 generator) or (ozone near10 (gas or atmospphere)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:11 |
| 19 | 26080 | (ozone near10 generator) or (ozone near10 (gas or atmosphere)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:11 |
| 20 | 21812 | (wafer or semiconductor or substrate) same (ozone near10 generator) or (ozone near10 (gas or atmosphere)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:12 |
| 21 | 11644 | (ozone near10 generator) or (ozone near10 (gas or atmosphere)) same ((wafer or semiconductor or substrate) nrat20 (spin or spinning or rotor or rotate or rotary or turn or turning or rotating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:13 |
| 22 | 8251 | (ozone near10 generator) or (ozone near10 (gas or atmosphere)) same ((wafer or semiconductor or substrate) near20 (spin or spinning or rotor or rotate or rotary or turn or turning or rotating)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:14 |
| 23 | 8169 | (ozone near10 generator) or (ozone near10 (gas or atmosphere)) same ((wafer or semiconductor or substrate) near20 (spin or spinning or rotor or rotate or rotary or turn or turning or rotating)) same (sprayer or spray or spraying or jet or nozzle) near15 ((water or chemical or liquid or chemicals or acid or solvent)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:16 |
| 24 | 219 | ((ozone near10 generator) or (ozone near10 (gas or atmosphere)) same ((wafer or semiconductor or substrate) near20 (spin or spinning or rotor or rotate or rotary or turn or turning or rotating)) same (sprayer or spray or spraying or jet or nozzle) near15 ((water or chemical or liquid or chemicals or acid or solvent))) and 134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:16 |

| 25 | 2579 | ((ozone near10 generator) or (ozone near10 (gas or atmosphere))) same ((wafer or semiconductor or substrate) near20 (spin or spinning or rotor or rotate or rotary or turn or turning or rotating)) same (sprayer or spray or spraying or jet or nozzle) near15 ((water or chemical or liquid or chemicals or acid or solvent))) and (134/$.ccls. or wash or washing or clean or cleaning or rinse or rinsing or decontaminate or decontamination or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 07:17 |
| – | 3 | "6235112" and (heat or heater or hot or heated or heating) | USPAT | 2004/04/20 07:18 |
| – | 1 | "6551409" and (heat or heater or hot or heated or heating) | USPAT | 2004/04/20 08:07 |
| – | 4 | "6325081" and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate) or ozone) | USPAT | 2004/04/20 08:10 |
| – | 4 | "6325081" and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) | USPAT | 2004/04/20 08:48 |
| – | 1 | "6684890" | USPAT | 2004/04/20 08:17 |
| – | 689 | 134/$.ccls. and (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) same (wafer or semiconductor) | USPAT | 2004/04/20 08:19 |
| – | 22 | "5378317" and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) | USPAT | 2004/04/20 08:51 |
| – | 1 | "5990060" and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) | USPAT | 2004/04/20 08:58 |
| – | 18868 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/04/20 09:01 |
| – | 547 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((heat or heater or hot or heated or heating) or (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) and 134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/04/20 09:06 |
| – | 371 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) and 134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT | 2004/04/20 10:53 |

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| — | 0 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) and 134/$.ccls. | IBM_TDB | 2004/04/20 10:21 |
| — | 1 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) and 134/$.ccls. | USOCR | 2004/04/20 10:26 |
| — | 1 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate)) and (washing or cleaning or clean or decontaminate or rinse or rinsing)134/$.ccls. | USOCR | 2004/04/20 10:27 |
| — | 302 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate)) and (washing or cleaning or clean or decontaminate or rinse or rinsing)134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/20 10:27 |
| — | 3068 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate)) and (washing or cleaning or clean or decontaminate or rinse or rinsing or decontaminating) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/20 10:27 |
| — | 132 | (((wafer or semiconductor or substrate) near15 (batch or boat or carrier)) and ((wafer or semiconductor or substrate) near15 (single or individual))) and ((sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) or ozone) and 134/$.ccls. and( (raised or raising) and (lowered or lowering)) | USPAT; US-PGPUB | 2004/04/20 11:18 |
| — | 2 | ((wafer or semiconductor or substrate) near25 (spin or spinning or turn or turning or rotate or rotating or rotor)) same (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) and 134/$.ccls. | USOCR | 2004/04/20 11:22 |
| — | 308 | ((wafer or semiconductor or substrate) near25 (spin or spinning or turn or turning or rotate or rotating or rotor)) same (sonic or ultrasonic or megasonic or hertz or MHZ or vibration or vibrate or oscillator or oscillation or oscillate) and 134/$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/04/21 06:00 |